

**IN THE CLAIMS**

1 (Previously Presented). A method comprising:

attaching ligands along a polymer bristle to form a semiconductor wafer cleaning brush.

2 (Original). The method of claim 1 including attaching ligands using a hydrolysis reaction.

3 (Previously Presented). The method of claim 1 including attaching ligands along a polyvinyl alcohol polymer.

4 (Previously Presented). The method of claim 1 including using a coupling agent to attach ligands along a polymer chain.

5 (Original). The method of claim 1 including attaching ligands to provide a hydrophilic property.

6 (Original). The method of claim 1 including attaching ligands to provide hydrophobic property.

7 (Original). The method of claim 1 including attaching ligands to provide a reducing agent property.

8 (Original). The method of claim 1 including attaching ligands to provide an oxidizing property.

9 (Original). The method of claim 1 including attaching ligands to provide an attraction to a specific material.

10 (Currently Amended). The method of claim 1 including attaching ligands to change a [[the]] zeta potential.

11 (Original). The method of claim 1 including attaching a ligand having a subchain to the polymer.

12 (Original). The method of claim 11 including attaching a moiety to said subchain to provide a desired property to said ligand.

13 (Previously Presented). A method comprising:

cleaning a semiconductor wafer using a polymer brush having ligands attached along a polymer.

14 (Original). The method of claim 13 including using a brush having ligands attached to polyvinyl alcohol polymer bristles.

15 (Original). The method of claim 13 including using a brush having ligands that provide a hydrophilic property.

16 (Original). The method of claim 13 including using a brush having ligands that provide a hydrophobic property.

17 (Original). The method of claim 13 including using a brush having ligands that provide a reducing agent property.

18 (Original). The method of claim 13 including using a brush having ligands that provide an oxidizing property.

19 (Original). The method of claim 13 including using a brush having ligands that are attracted to a specific material.

20 (Currently Amended). The method of claim 13 including using a brush having ligands to establish having a positive zeta potential in a media.

21 (Currently Amended). The method of claim 13 including using a brush having ligands to establish having a negative zeta potential in a media.

22 (Original). The method of claim 13 including using a brush having a ligand having a subchain of at least two carbon atoms.

23 (Previously Presented). The method of claim 22 including using a brush having a moiety on said subchain to provide a property to said ligand.

Claims 24-34 (Canceled).